L Number	Hits	Search Text	DB	Time stamp
1	892	((wash$3 or clean$3 or spray$3 or pure or ultrapure) near3 (water)) and (water with (low near2 (resistance or resistivity)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/23 11:15
2	140	((wash$3 or clean$3 or spray$3 or pure or ultrapure) near3 (water)) same (water with (low near2 (resistance or resistivity)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/23 11:28
3	9	((wash$3 or clean$3) with (pure or ultrapure) near3 (water)) same (water with (low near2 (resistance or resistivity)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/23 11:29
4	240	((wash$3 or clean$3) with (pure or ultrapure) near3 (water)) same (water near3 ((resistance or resistivity)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/23 11:30
5	23	((wash$3 or clean$3) with (pure or ultrapure) near3 (water)) same (water near3 ((resistance or resistivity))) same (dust or static)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/23 11:30
-	204	(Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:22
-	177	(Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:05
-	2	(Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier)) with surfactant)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 14:55
-	40	(Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier))) same (dust$3 or particle or particulate or contamin$8)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 14:56

–	38	((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier))) same (dust$3 or particle or particulate or contamin$8)) not ((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier)) with surfactant))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 14:56
–	137	((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier)))) not ((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier))) same (dust$3 or particle or particulate or contamin$8))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:00
–	12	(Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (cassette)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:07
–	9	((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (cassette)))) not (((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier)))) not ((Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holding or housing or carrier))) same (dust$3 or particle or particulate or contamin$8)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:06
–	19	(Munakata.in. or (Shin adj Etsu).as.) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (transport$6)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:08
–	896	(427/230,235).CCLS.	USPAT; US-PGPUB	2003/12/22 15:08
–	806	(427/352,353,354).CCLS.	USPAT; US-PGPUB	2003/12/22 15:08
–	3616	(427/372.2,379,384).CCLS.	USPAT; US-PGPUB	2003/12/22 15:08

–	1369	(427/430.1).CCLS.	USPAT; US-PGPUB	2003/12/22 15:09
–	717	(438/125).CCLS.	USPAT; US-PGPUB	2003/12/22 15:09
–	2870	(206/308.1,524.1,524.6,525,526,832).CCLS.	USPAT; US-PGPUB	2003/12/22 15:09
–	517	(206/524.3).CCLS.	USPAT; US-PGPUB	2003/12/22 15:09
–	10391	((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)	USPAT; US-PGPUB	2003/12/22 15:14
–	16	(((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((wafer or semiconductor) same (surfactant))	USPAT; US-PGPUB	2003/12/22 15:12
–	0	((206/524.3).CCLS.) and ((wafer or semiconductor) same (surfactant))	USPAT; US-PGPUB	2003/12/22 15:11
–	40	((206/524.3).CCLS.) and ((surfactant))	USPAT; US-PGPUB	2003/12/22 15:12
–	0	(((206/524.3).CCLS.) and ((surfactant))) and (wafer or semiconductor)	USPAT; US-PGPUB	2003/12/22 15:12
–	402	(((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or deposit$3 or film or layer or immers$5 or soak$3 or dip or dipped or dipping or submer$8) with surfactant)	USPAT; US-PGPUB	2003/12/22 15:14
–	295	((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or deposit$3 or film or layer or immers$5 or soak$3 or dip or dipped or dipping or submer$8) with surfactant)) and (dust$3 or particle or particulate or contamin$8)	USPAT; US-PGPUB	2003/12/22 15:15
–	140	((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or deposit$3 or film or layer or immers$5 or soak$3 or dip or dipped or dipping or submer$8) with surfactant)) and (dust$3 or contamin$8)	USPAT; US-PGPUB	2003/12/22 15:15
–	42	((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or deposit$3 or film or layer or immers$5 or soak$3 or dip or dipped or dipping or submer$8) with surfactant)) and (((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier or cassette or transport$6)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:20

-	7	((206/524.3).CCLS.) and (((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier or cassette or transport$6)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:21
-	439	(((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier)))	USPAT; US-PGPUB	2003/12/22 15:51
-	71	((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier)))) and ((prevent$5 or eliminat$5 or reduc$6 or lower$3 or stop$4) near3 (dust$3 or particle or particulate or contamin$8))	USPAT; US-PGPUB	2003/12/22 15:24
-	255	(((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or housing or carrier or cartridge)))	USPAT; US-PGPUB	2003/12/22 15:35
-	211	((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or housing or carrier or cartridge)))) not (((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier)))) and ((prevent$5 or eliminat$5 or reduc$6 or lower$3 or stop$4) near3 (dust$3 or particle or particulate or contamin$8)))	USPAT; US-PGPUB	2003/12/22 15:29

–	129	(surfactant or scourol) and (((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or housing or carrier or cartridge or case)))	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:48
–	96	((surfactant or scourol) and (((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or housing or carrier or cartridge or case)))) and (coat$3 or wash$3 or clean$3 or film or layer or deposit$3 or immers$5 or submer$6 or soak$3 or dip or dipped or dipping)	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:38
–	33	((surfactant or scourol) and (((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or housing or carrier or cartridge or case)))) not (((surfactant or scourol) and (((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or housing or carrier or cartridge or case)))) and (coat$3 or wash$3 or clean$3 or film or layer or deposit$3 or immers$5 or submer$6 or soak$3 or dip or dipped or dipping))	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 15:48
–	178	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) same ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier))) same (surfactant or scourol)	USPAT; US-PGPUB	2003/12/22 16:03
–	245	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer or wash$3 or clean$3) same ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier))) same (surfactant or scourol)	USPAT; US-PGPUB	2003/12/22 15:53
–	958	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) same ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier))) same (antistatic$3 or (anti adj static$3) or ((prevent$4 or eliminat$3 or reduc$5 or stop$4 or lower$3) near3 (dust or contamin$5 or particle or particulate)))	USPAT; US-PGPUB	2003/12/22 16:20
–	11	(((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) same ((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier))) same (antistatic$3 or (anti adj static$3) or ((prevent$4 or eliminat$3 or reduc$5 or stop$4 or lower$3) near3 (dust or contamin$5 or particle or particulate)))) and ((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.))	USPAT; US-PGPUB	2003/12/22 16:05

—	38	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) same ((wafer or chip or substrate or disc or disk) near3 ((storage or storing or holding or housing or transport$5) near2 (case or box or holder or carrier)))) same (antistatic$3 or (anti adj static$3) or ((prevent$4 or eliminat$3 or reduc$5 or stop$4 or lower$3) near3 (dust or contamin$5 or particle or particulate)))	USPAT; US-PGPUB	2003/12/22 16:12
—	62	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) same ((wafer or chip or substrate or disc or disk) near3 ((storage or storing or holding or housing or transport$5) near2 (case or box or holder or carrier)))) and (surfactant)	USPAT; US-PGPUB	2003/12/22 16:19
—	62	(((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) same ((wafer or chip or substrate or disc or disk) near3 ((storage or storing or holding or housing or transport$5) near2 (case or box or holder or carrier)))) and (surfactant)) not ((((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)) and ((coat$3 or surfactant or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with ((wafer or chip or substrate or disc or disk) near2 (storage or storing or box or holder or holding or	USPAT; US-PGPUB	2003/12/22 16:13
—	33389	housing or carrier dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant))	USPAT; US-PGPUB	2003/12/22 16:31
—	401	(((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant))) and (((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.))	USPAT; US-PGPUB	2003/12/22 16:19
—	0	((((((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant))) and (((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.))) and ((wafer or chip or substrate or disc or disk) near3 ((storage or storing or holding or housing or transport$5) near2 (case or box or holder or carrier))))	USPAT; US-PGPUB	2003/12/22 16:22

-	41	(((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier or cartridge or transport$8))) and ((((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant))) and (((427/230,235).CCLS.) ((427/352,353,354).CCLS.) ((427/372.2,379,384).CCLS.) ((427/430.1).CCLS.) ((438/125).CCLS.) ((206/308.1,524.1,524.6,525,526,832).CCLS.) ((206/524.3).CCLS.)))	USPAT; US-PGPUB	2003/12/22 16:22
-	2926	(((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier or cartridge or transport$8))) and (((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant)))	USPAT; US-PGPUB	2003/12/22 16:32
-	34	((((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant))) and ((wafer or chip or substrate or disc or disk) near3 ((storage or storing or holding or housing or transport$5) near2 (case or box or holder or carrier))))	USPAT; US-PGPUB	2003/12/22 16:22
-	144	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) with (surfactant)) same ((prevent$5 or eliminat$3 or reduc$5 or stop$4 or lower$3) near3 (dust$3 or contamin$8))	USPAT; US-PGPUB	2003/12/22 16:34
-	7772	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) near5 (surfactant))	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 16:33
-	28	(((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) near5 (surfactant))) and (((wafer or chip or substrate or disc or disk) near3 (storage or storing or case or box or holder or holding or housing or carrier or cartridge or transport$8)))	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 16:32
-	322	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) near5 (surfactant)) and (dust$3 or contamin$8)	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 16:34
-	296	((coat$3 deposit$3 or film or layer) near5 (surfactant)) and (dust$3 or contamin$8)	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 16:39
-	55	((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) near3 (surfactant)) and ((prevent$5 or eliminat$3 or reduc$5 or stop$4 or lower$3) near3 (dust$3 or contamin$8))	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 16:35
-	47	((coat$3 deposit$3 or film or layer) near5 (surfactant)) and (dust$3 or contamin$8) and dry$3	EPO; JPO; DERWENT; IBM_TDB	2003/12/22 16:39
-	41	(((coat$3 deposit$3 or film or layer) near5 (surfactant)) and (dust$3 or contamin$8) and dry$3) not (((coat$3 or dip or dipped or dipping or immers$4 or submer$5 or deposit$3 or film or layer) near3 (surfactant)) and ((prevent$5 or eliminat$3 or reduc$5 or stop$4 or lower$3) near3 (dust$3 or contamin$8)))	EPO; JPO; DERWENT; IBM_TDB	2003/12/23 11:13